Preface

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The 5th KIST-OPU-ECUST-TKU Joint Symposium on Advanced Materials and Application (5th-JSAMA).

From 25 to 27 September 2016, the 5th KIST-OPU-ECUST-TKU Joint Symposium on Advanced Materials and Application was held at the Korea Institute of Science and Technology (KIST) in Seoul, South Korea, under the title “Next Generation Photochemistry and Photophysics: From Materials to Applications.” The symposium was funded by the Korean National Research Foundation and KIST’s Materials and Life Science Research Division. Its purpose was to establish a close relationship among four major organizations in Asia—Osaka Prefecture University (OPU, Japan), East China University of Science and Technology (ECUST, China), TamKang University (TKU, Taiwan), and KIST (South Korea)—and to exchange research personnel and technical information for conducting joint research in the field of materials science.

This cooperation effort was initiated by the global KIST project in 2010. The 1st KIST-OPU Joint Symposium dates back to 2 May 2011, and was held at KIST with full funding from the global KIST project. In September 2012, the 2nd OPU-KIST Joint Symposium was held at OPU in Osaka, and the 3rd ECUST-OPU-KIST Joint Symposium was conducted at ECUST in Shanghai in August 2013. In September 2014, the 4th TKU-ECUST-OPU-KIST Joint Symposium was held at TamKang University (TKU) in Tamsui.

The 5th KIST-OPU-ECUST-TKU Joint Symposium was attended by 67 scientists and students from KIST, and more than 50 people from overseas. The event featured 22 oral presentations and 44 poster presentations, and was a great success with valuable discussions and brain-storming for future collaborations.

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This special issue of *Research on Chemical Intermediates* includes contributions from presenters and attendees at the symposium, in the hope of covering the latest developments in materials science, with especial emphasis on photochemistry and physics. The 19 papers included in this issue were carefully peer-reviewed and revised for publication.

I would like to express my sincere gratitude to the organizing committee and many others who contributed to the 5th KIST-OPU-ECUST-TKU Joint Symposium. My sincere thanks also go to the authors who submitted manuscripts for this special issue, and to the reviewers and publishers who spent much time and effort reviewing and editing them.

So-Hye Cho

Principal researcher/symposium chair

Guest editor

The 5th KIST-OPU-ECUST-TKU Joint Symposium on Advanced Materials and Application (5th-JSAMA)

KIST, Seoul, South Korea, 25–27 September 2016

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